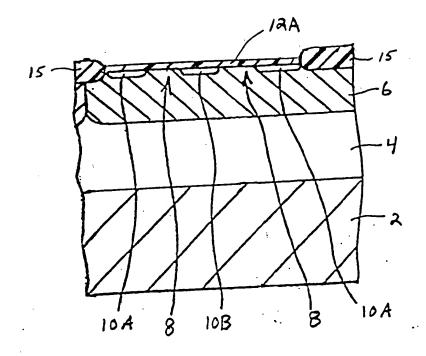
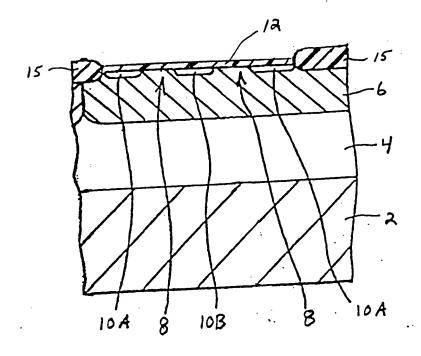


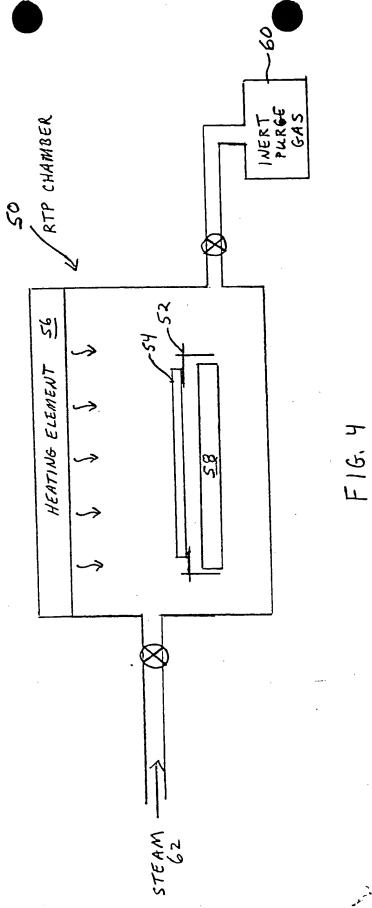
F1G. 1

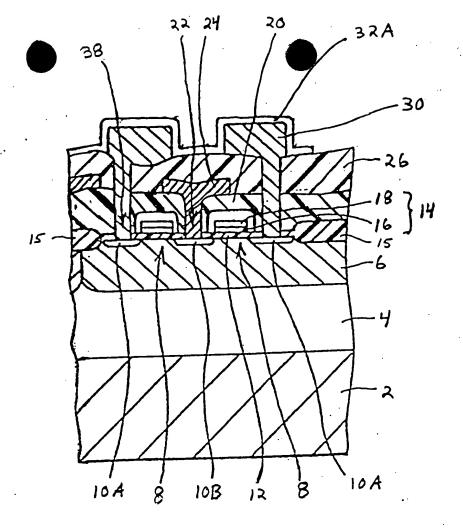


F1G. 2

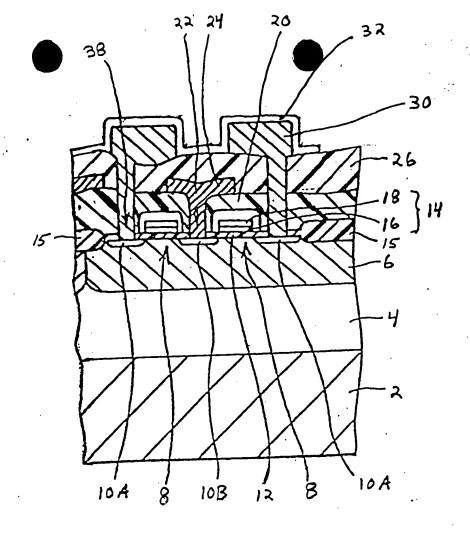


F1G. 3

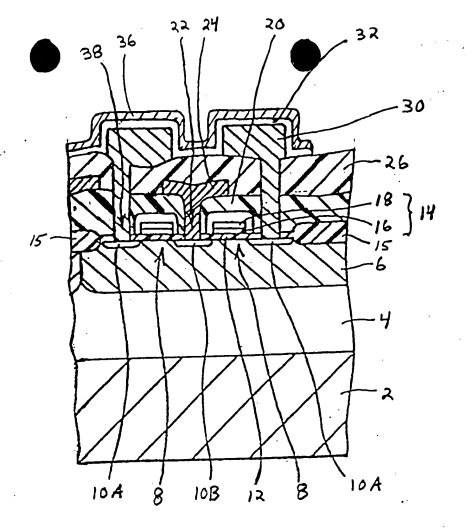




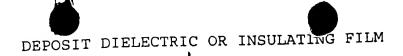
F1G. 5



F1G. 6



F1G. 7



SUBJECT THE INSULATING FILM TO A HEAT TREATMENT IN AN AMBIENT COMPRISING A STABILIZING GAS INCLUDING A GAS SELECTED FROM THE GROUP CONSISTING OF  $N_2$ ,  $O_2$ ,  $O_3$ , NO, OR  $N_2O_1$ 

SUBJECT THE INSULATING FILM TO A WET OXIDATION IN A RAPID THERMAL PROCESS (RTP) CHAMBER

FIG. 8